



# 電界効果によるグラフェンの 電気伝導変調

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マテリアル工学専攻

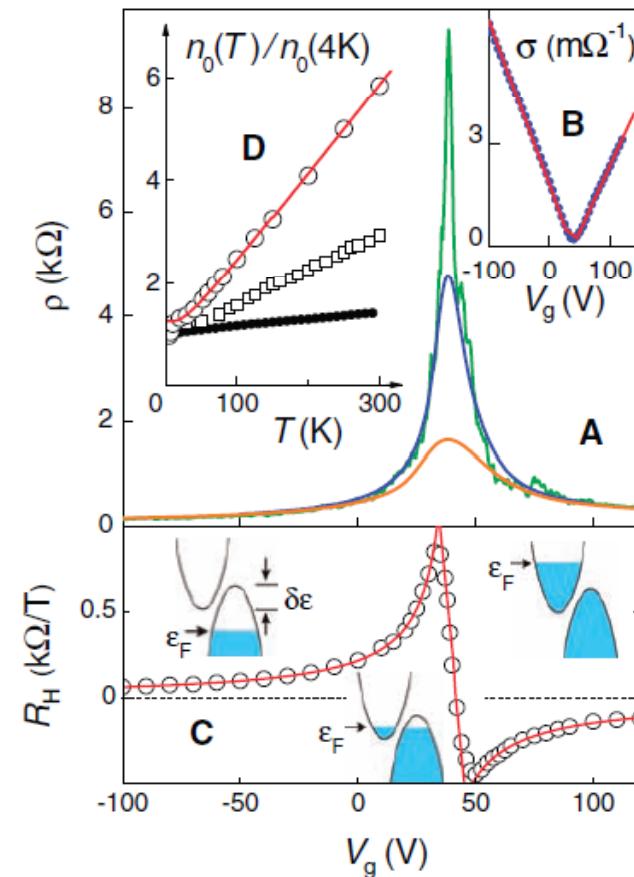
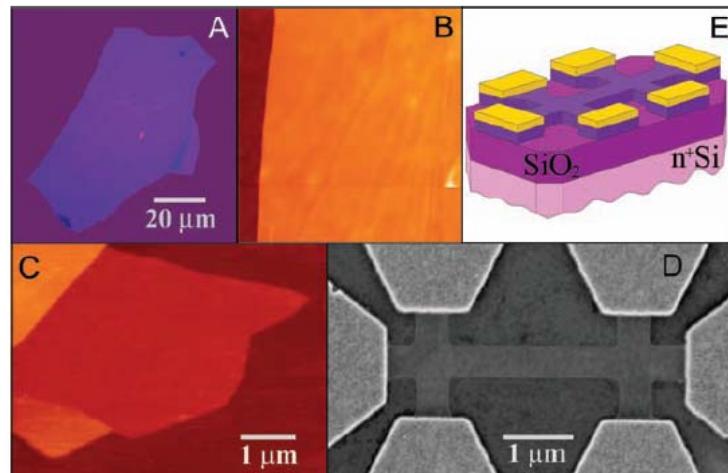
*toriumi@material.t.u-tokyo.ac.jp*  
*http://www.adam.t.u-tokyo.ac.jp/*

@Lab.

# *Exciting Material, Graphene !*

## Electric Field Effect in Atomically Thin Carbon Films

K. S. Novoselov,<sup>1</sup> A. K. Geim,<sup>1\*</sup> S. V. Morozov,<sup>2</sup> D. Jiang,<sup>1</sup>  
Y. Zhang,<sup>1</sup> S. V. Dubonos,<sup>2</sup> I. V. Grigorieva,<sup>1</sup> A. A. Firsov<sup>2</sup>



*K. S. Novoselov et al. Science 306 (2004) 666.*

*The pioneering work in Manchester Univ.*

# *Outline*

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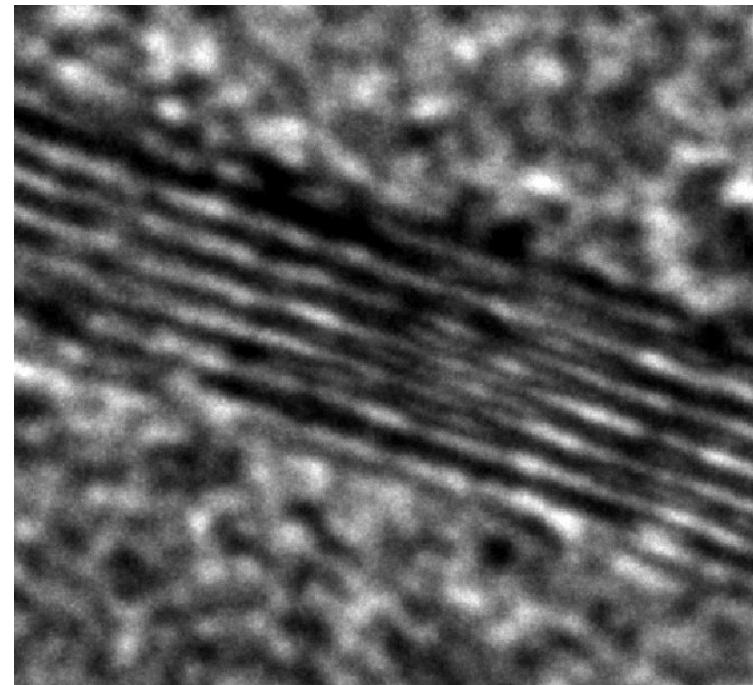
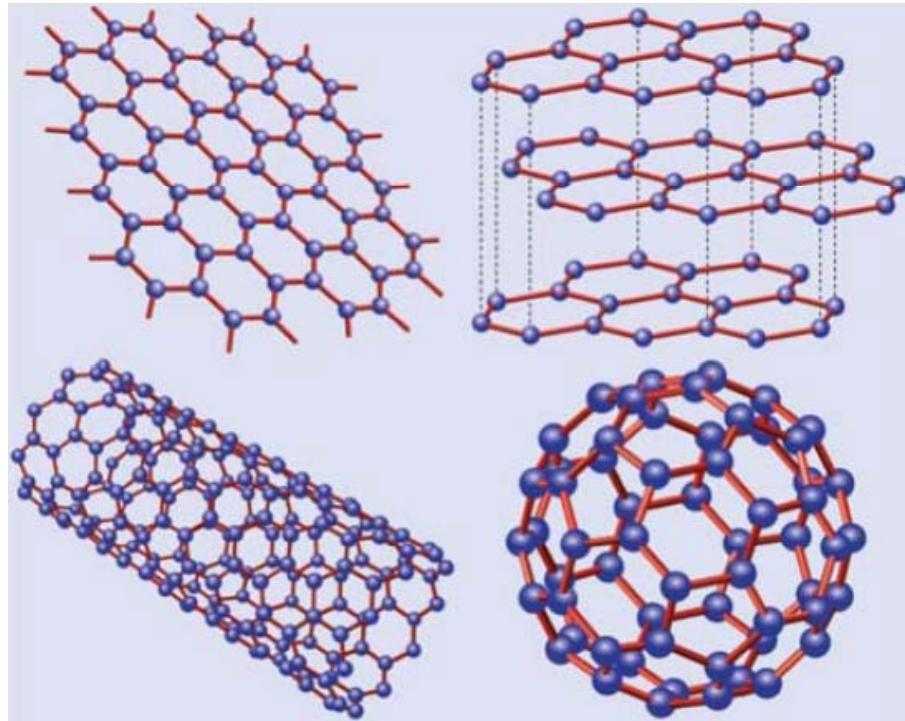
*1. Graphene Introduction*

*2. Electric Field Effects in Graphene*

*3. Possible Applications*

*4. Summary and Future Outlook*

# *Graphene*

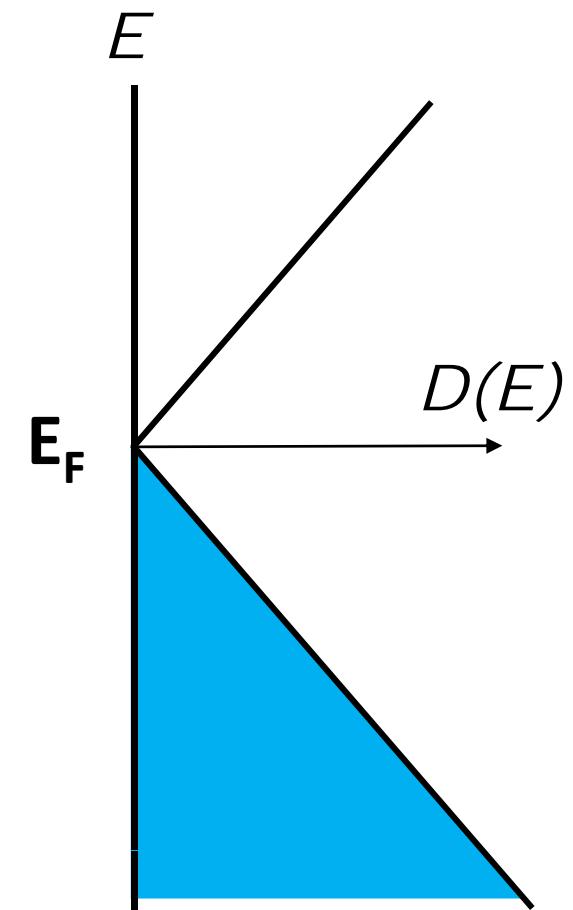
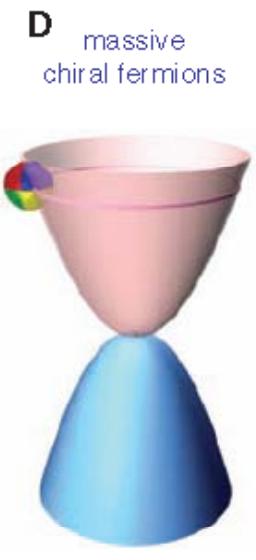
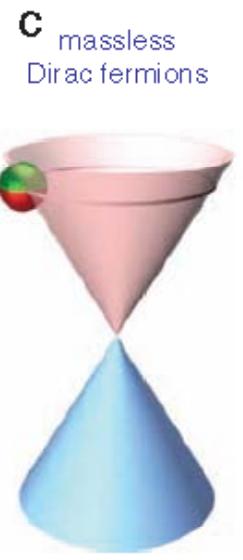
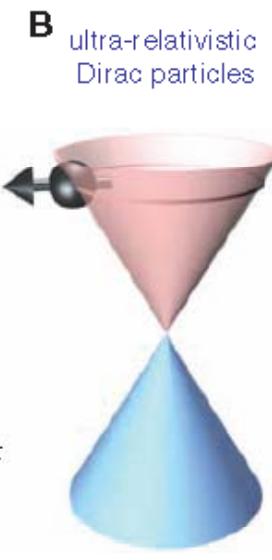
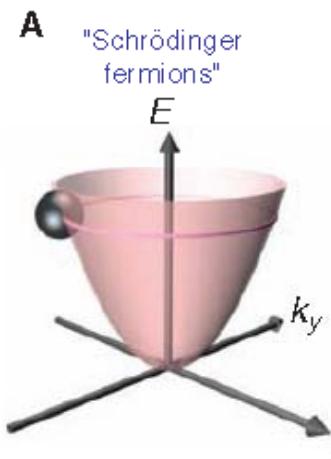


*TEM on 90 nm-thick  $SiO_2$  @Lab.*

*A. H. Castro Neto et al., Rev. Mod. Phys.  
81(2009)109.*

# *E - k Dispersion and Density of States*

*A great fun for condensed matter physicists*



A. K. Geim, Science, 324 (2009) 1530.

*Unique E-k dispersion and density of states.*

# *Advanced Peeling Technique !*

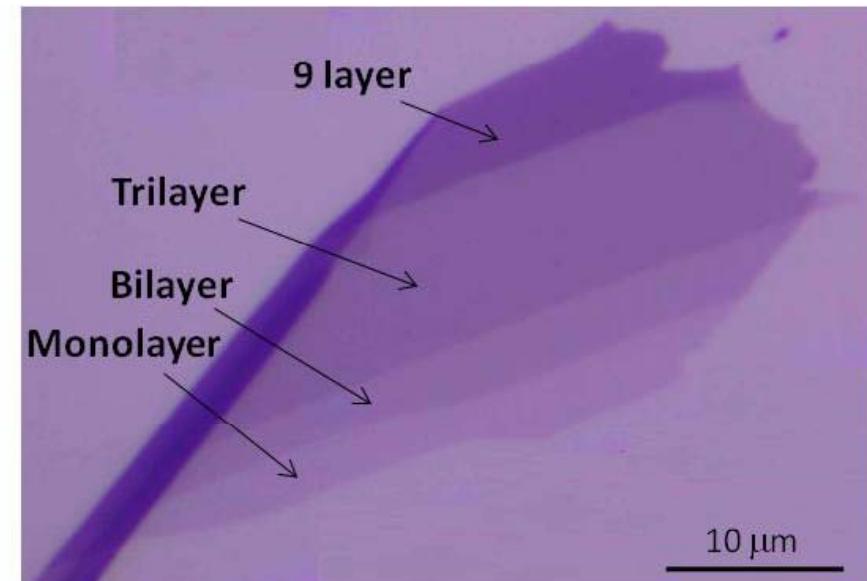
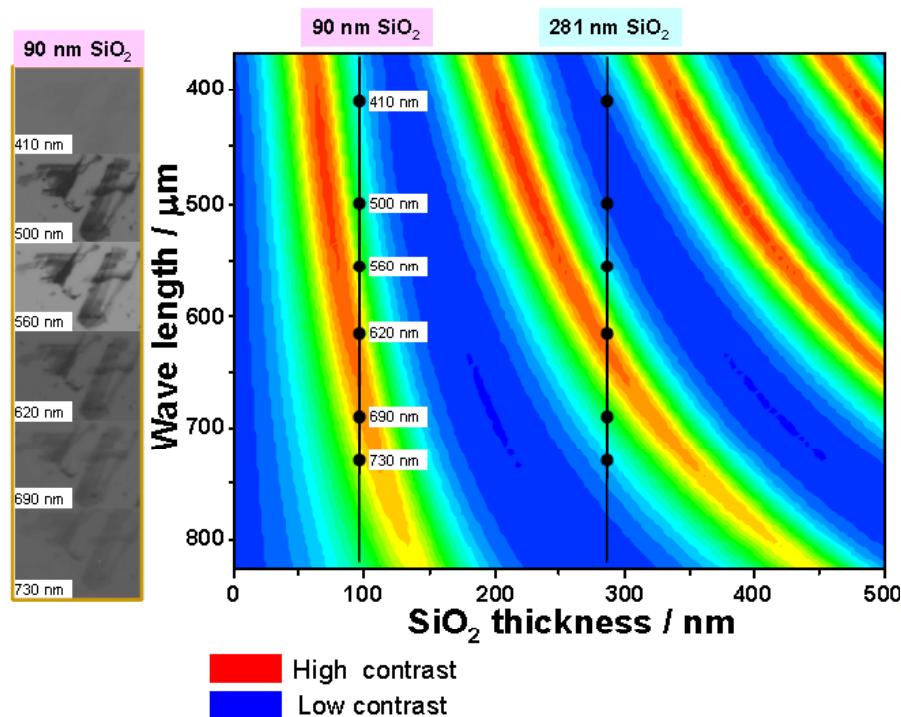
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# *Optical Contrast of Graphene on $SiO_2/Si$*

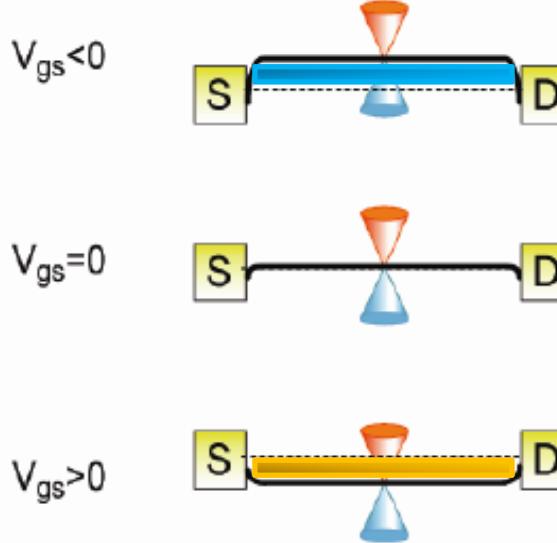
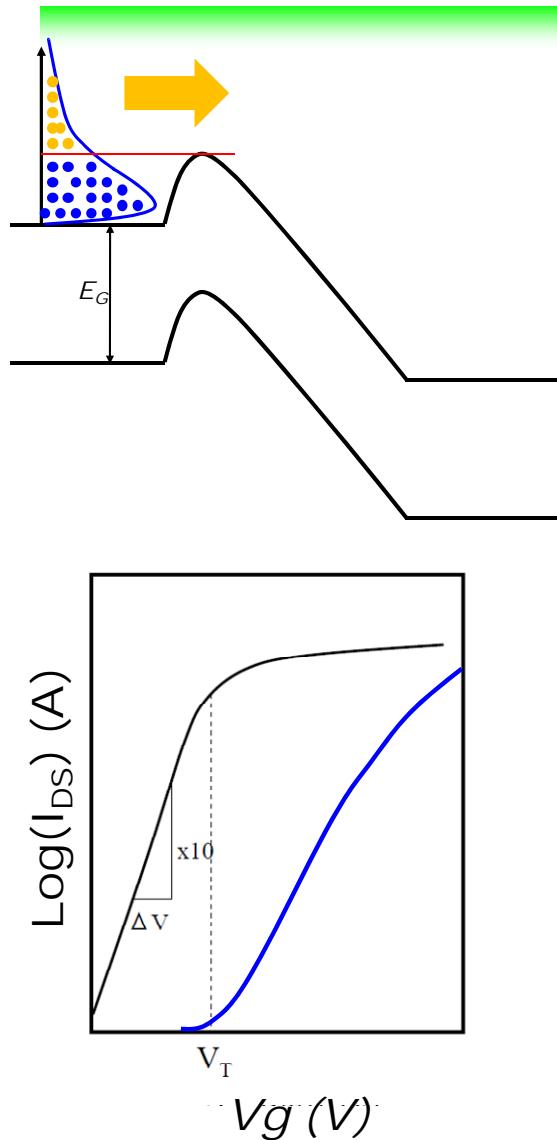
$$\text{contrast} = \frac{R_{\text{oxide}} - R_{\text{gra}}}{R_{\text{oxide}}}$$



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*A monolayer graphene on ~90 nm  $SiO_2$  is also visible by optical microscope.*

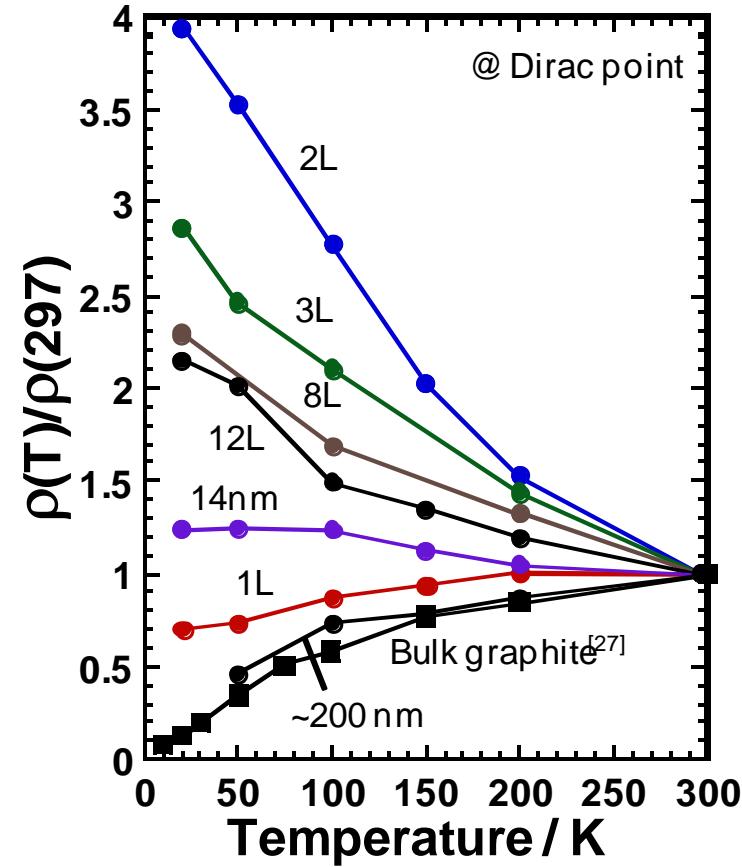
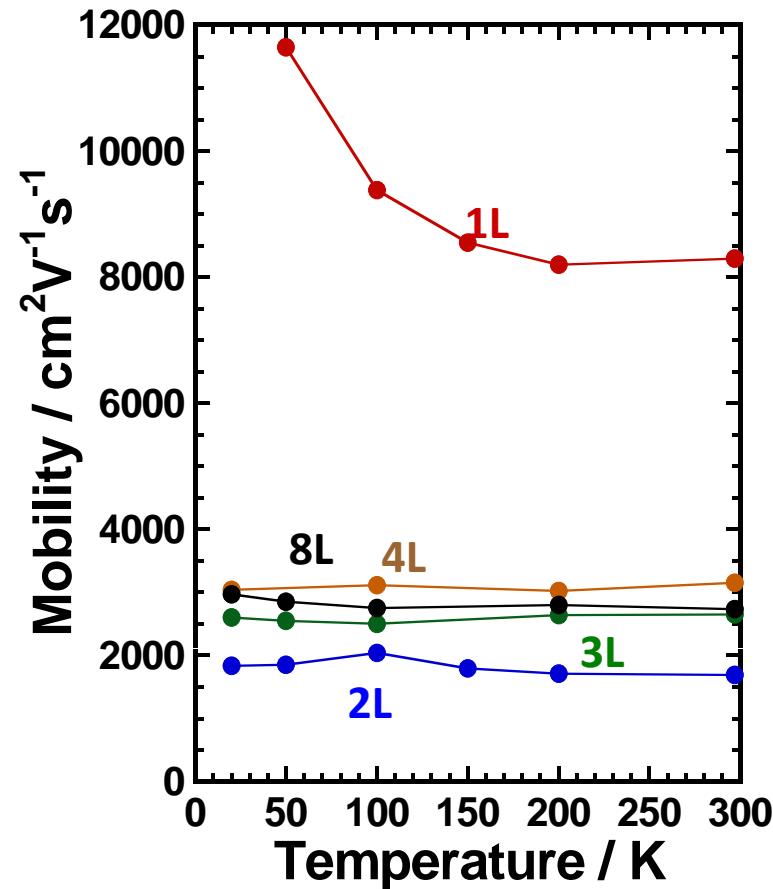
# *Conventional FET and Graphene FET*



*Z. Chen and J. Appenzeller, IEDM (2008).*

*Ambipolar Characteristics.*

# *Graphite to Graphene on $SiO_2$*

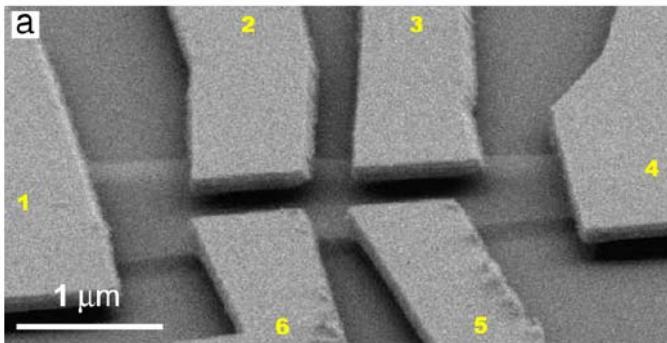


*K. Nagashio et al., JJAP 49 (2010).*

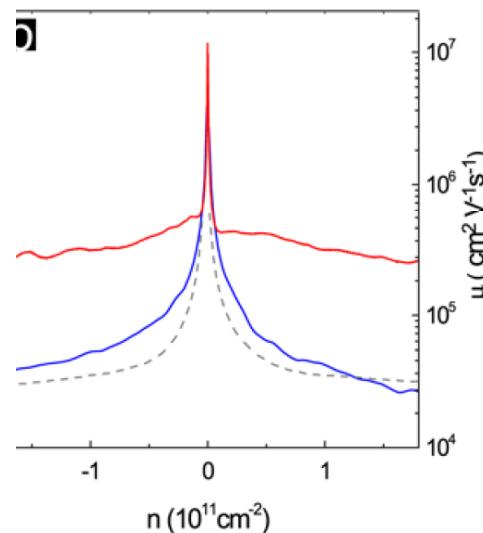
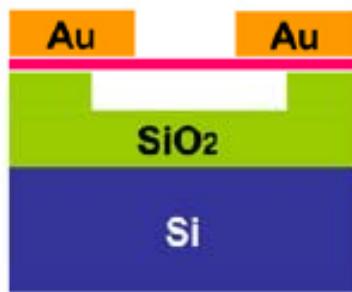
*Monolayer graphene is something special.*

# Graphene on Nothing and on BN

Suspended

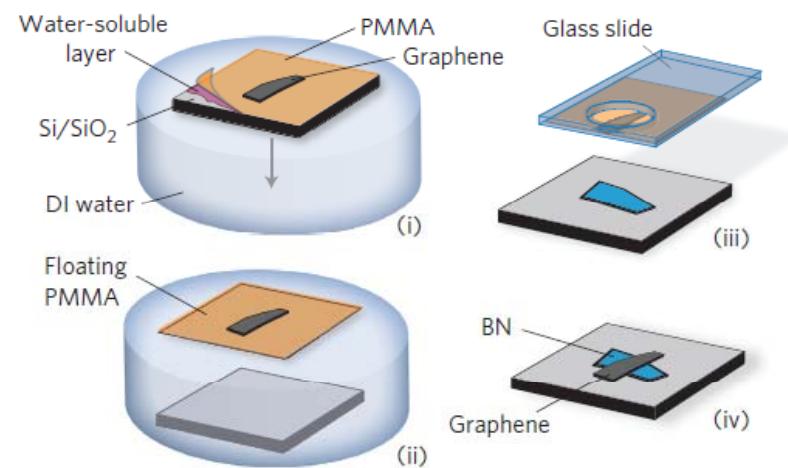


d

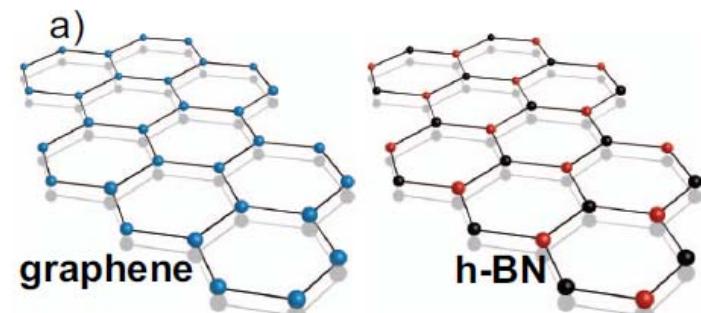


K. I. Bolotin et al., *SSC* 146 (2008) 351.

On BN

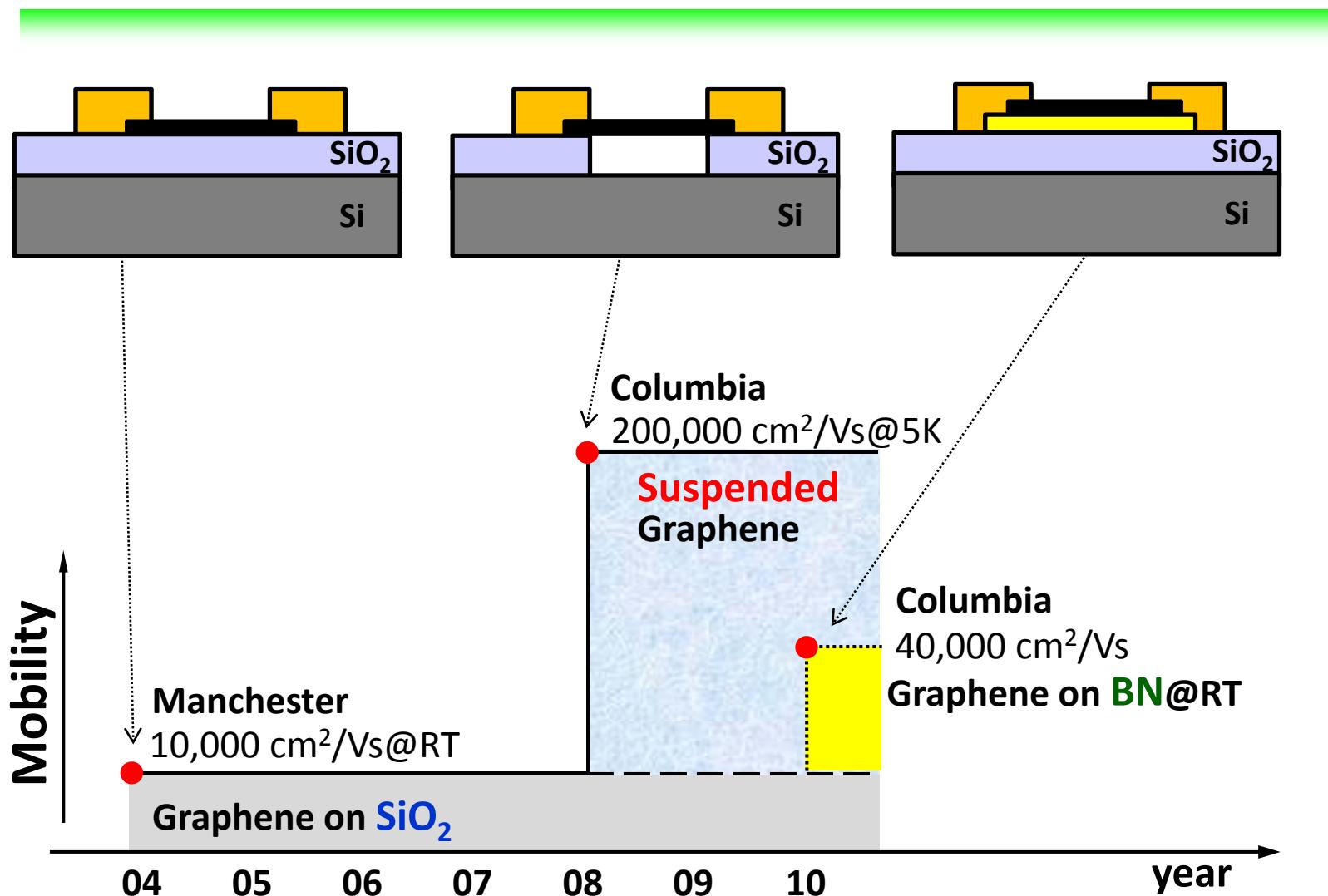


C. R. Dean et al., *Nature Nano.* 172 (2010) 722.

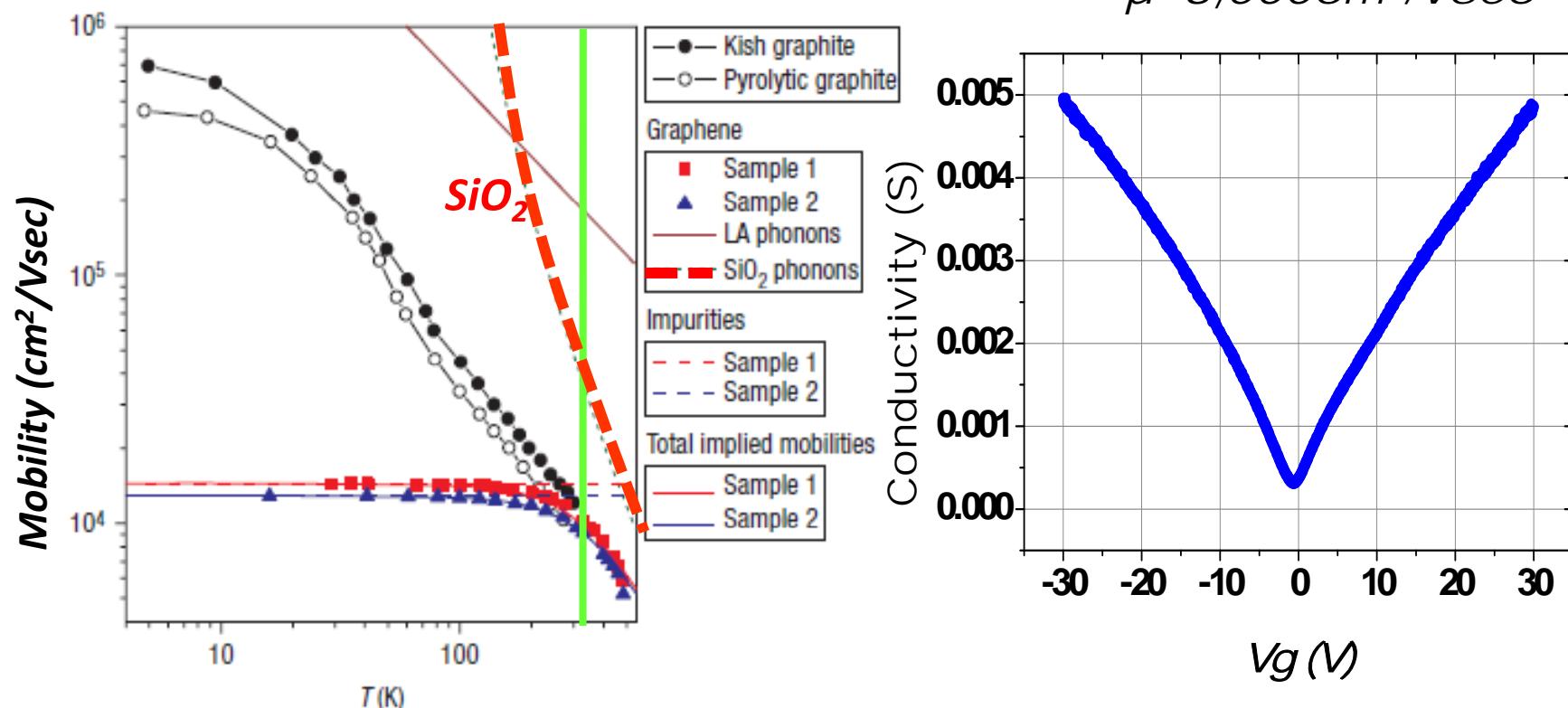


1.7% lattice mismatch

# *Mobility Limited by Interfacing Substrate*



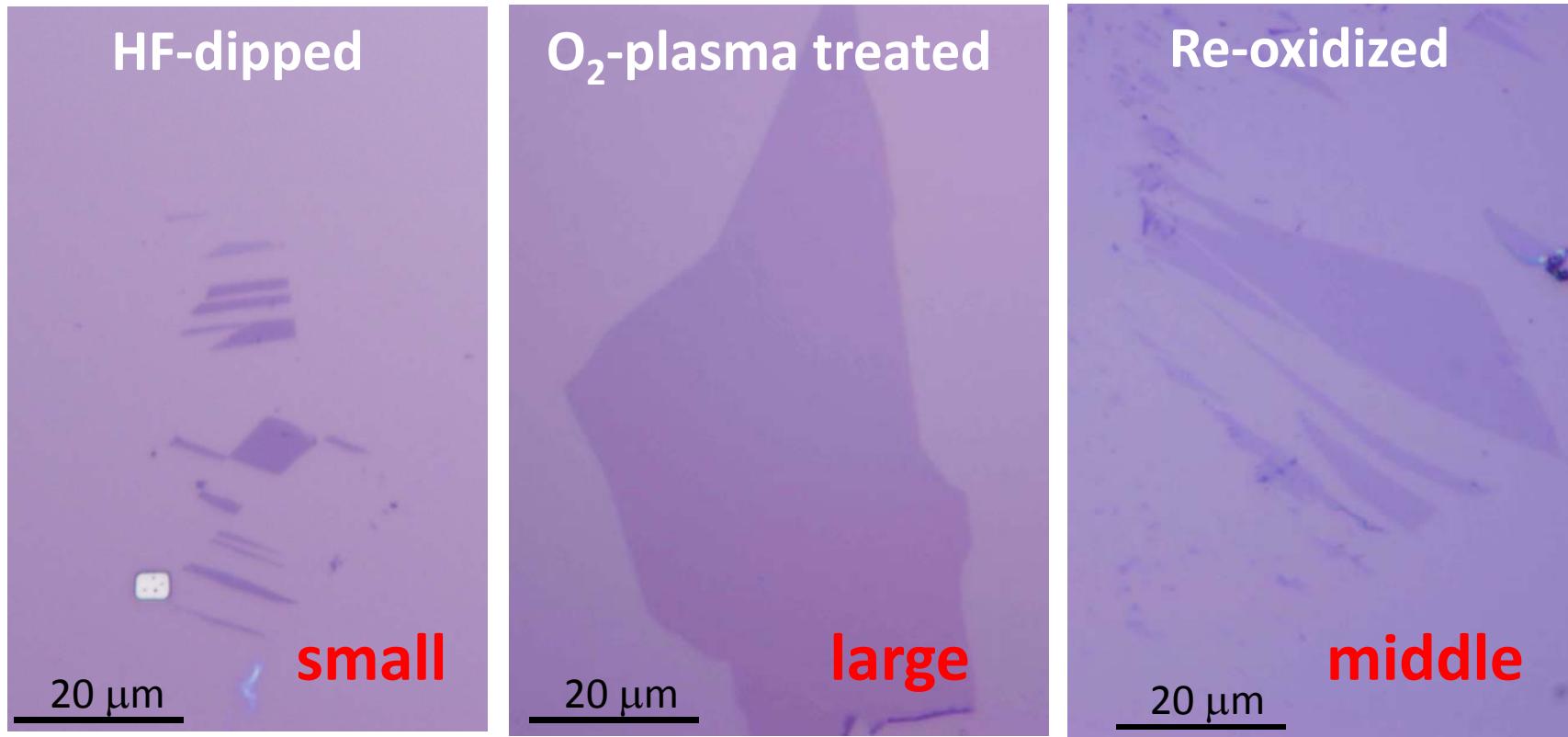
# Possible Scattering Mechanisms



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J-H Chen et al., Nature Nano. 3 (2008) 206.

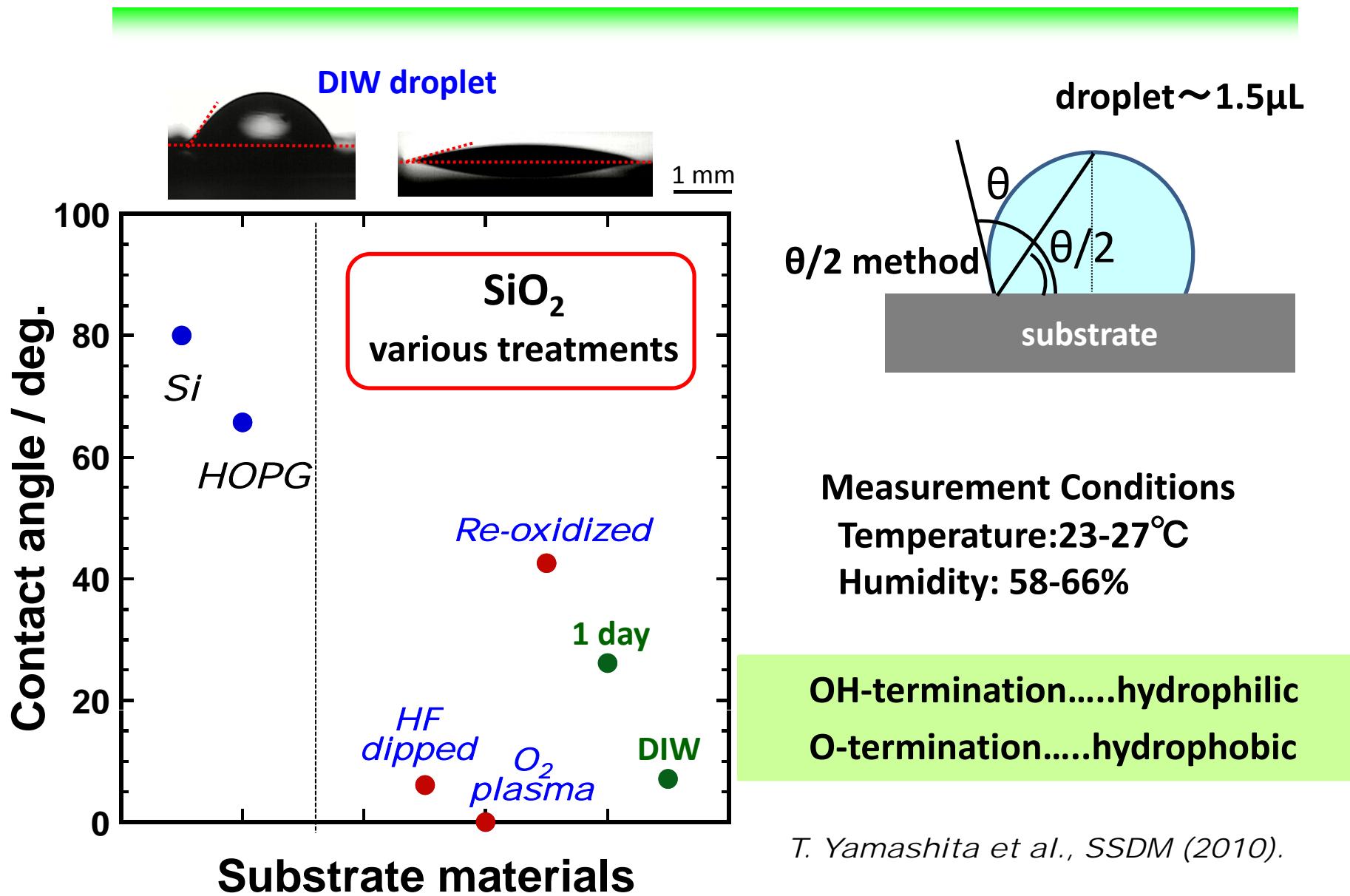
# *Graphene / $SiO_2$ Interaction*



@Lab.

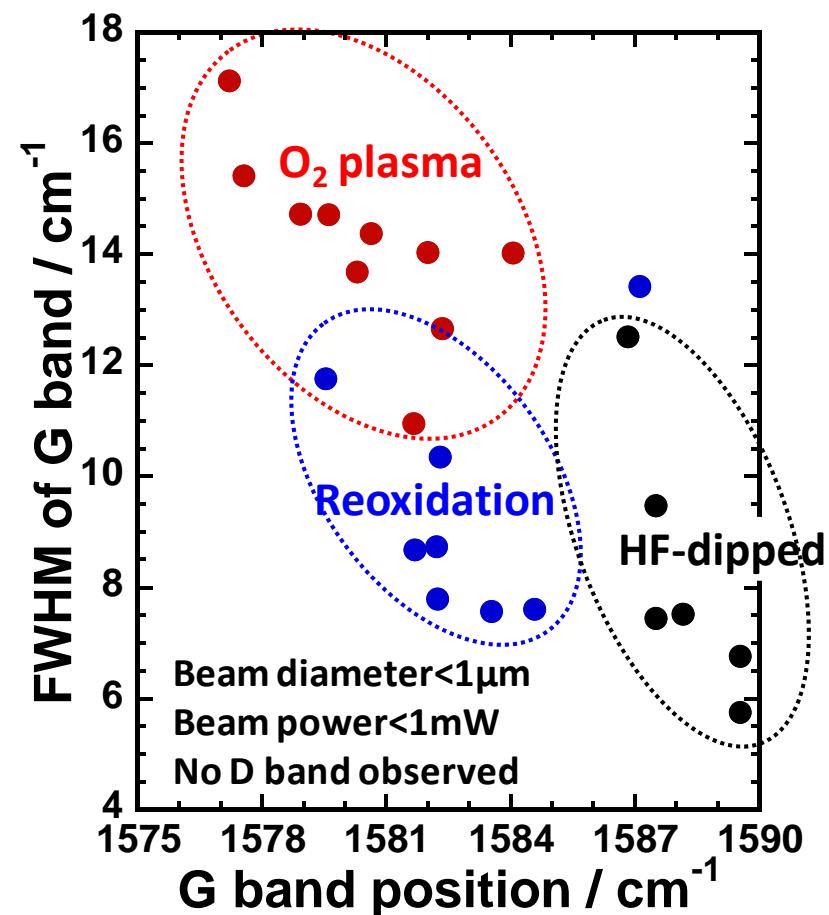
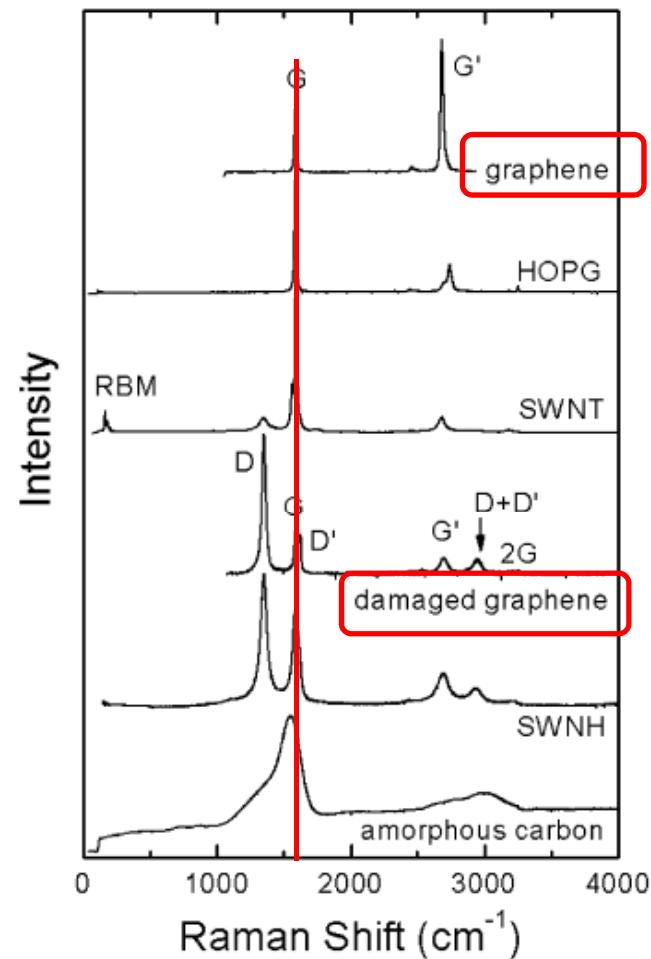
*The flake size depends on  $SiO_2$  surface treatment.*

# Contact Angles on Differently Treated $\text{SiO}_2$



T. Yamashita et al., SSDM (2010).

# *Effects of $SiO_2$ Surface on Raman G-band*



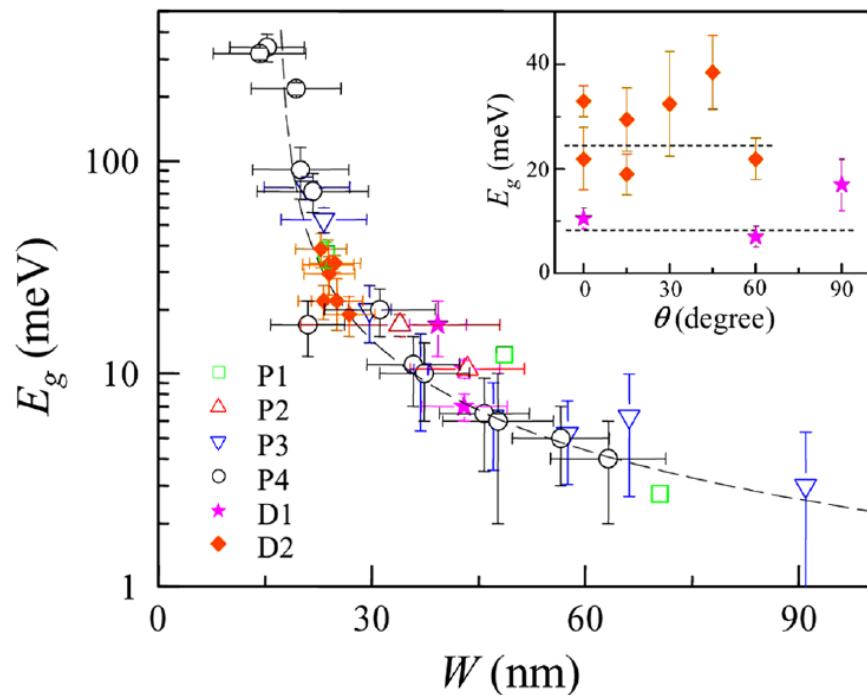
M. S. Dresselhaus et al., Nano Lett. 10(2010)751

K. Nagashio et al., IEDM (2010).

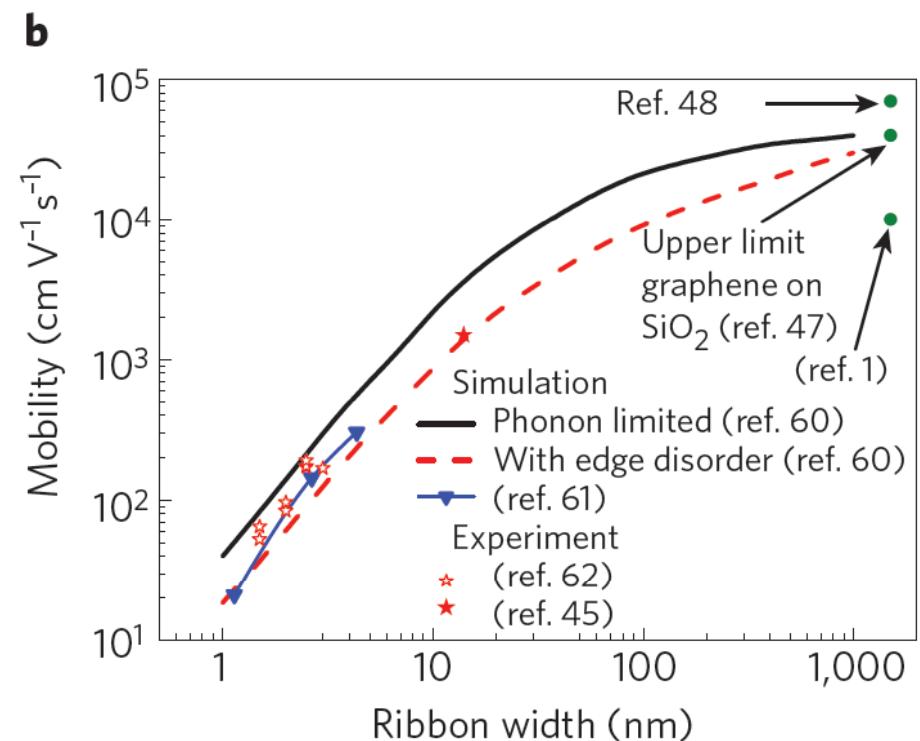
*A strong interaction between graphene and  $SiO_2$ .*

# *Intrinsic Challenges (1) - no band gap -*

## *Nano Ribbon*



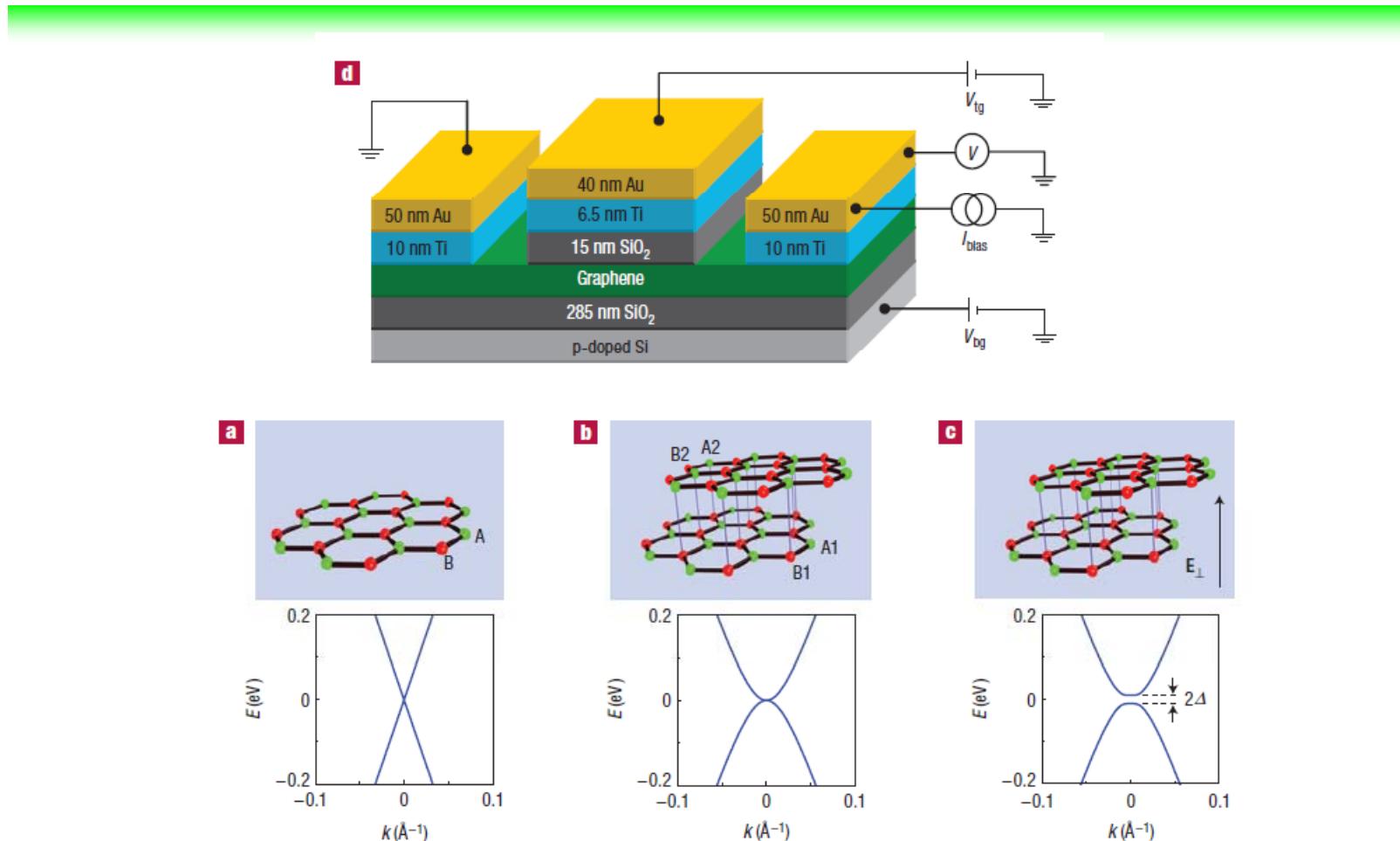
M. Y. Han et al., PRL 98(2007)206805.



F. Schwierz, Nature Nanotech. May 2010.

*Mobility is degraded as  $E_G$  is opened.*

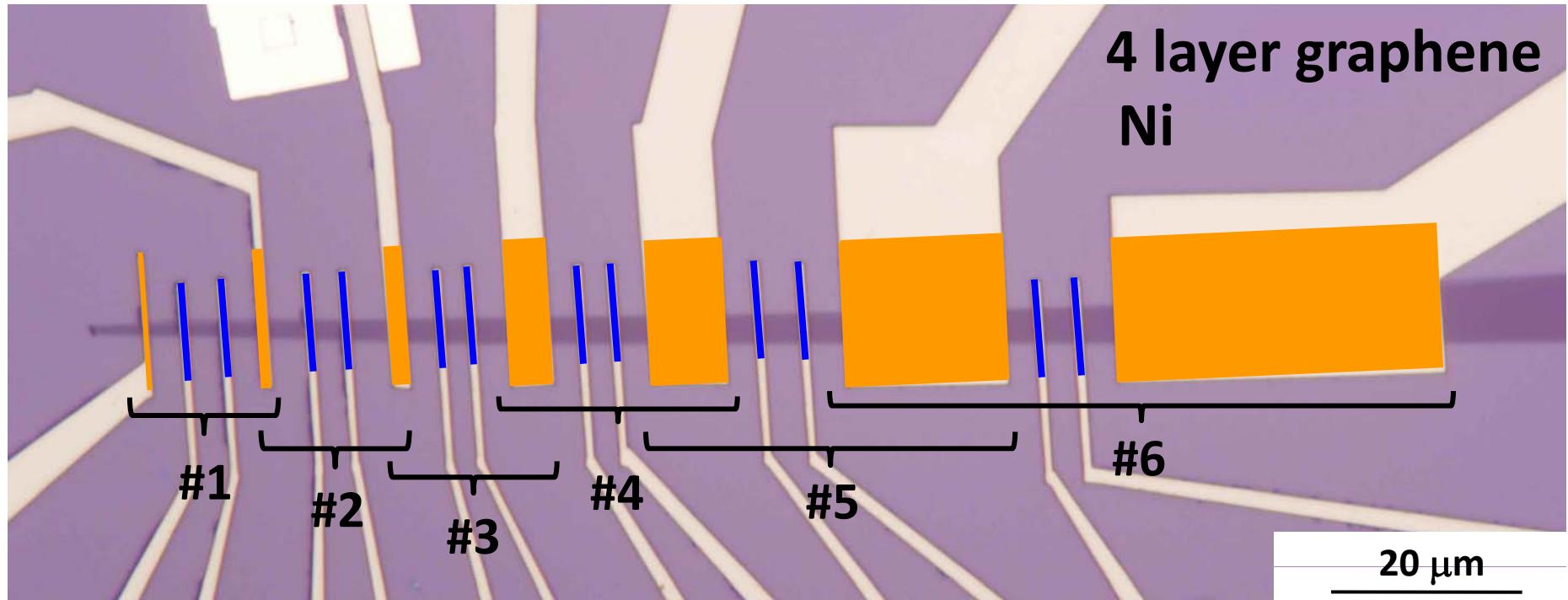
# Bi-layer Graphene



J. B. Oostinga et al., *Nature Materials* 7 (2008) 151.

Bi-layer graphene with double gates can open the gap!

## *Intrinsic Challenges (2) - contact resistance -*



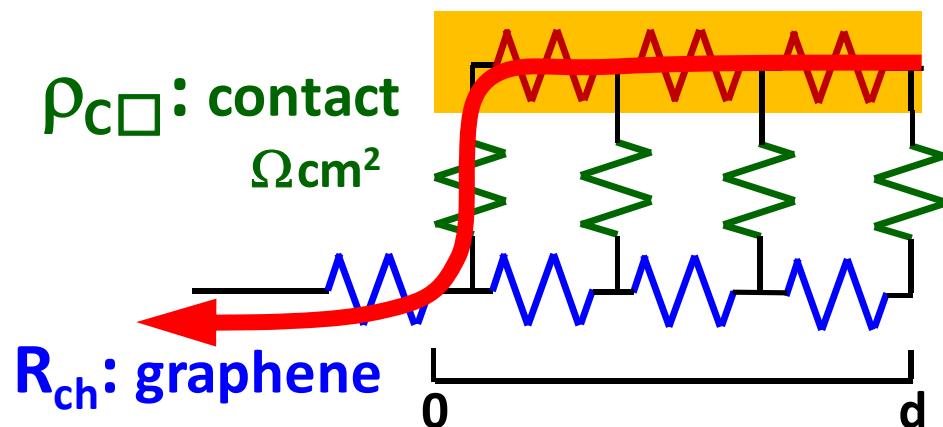
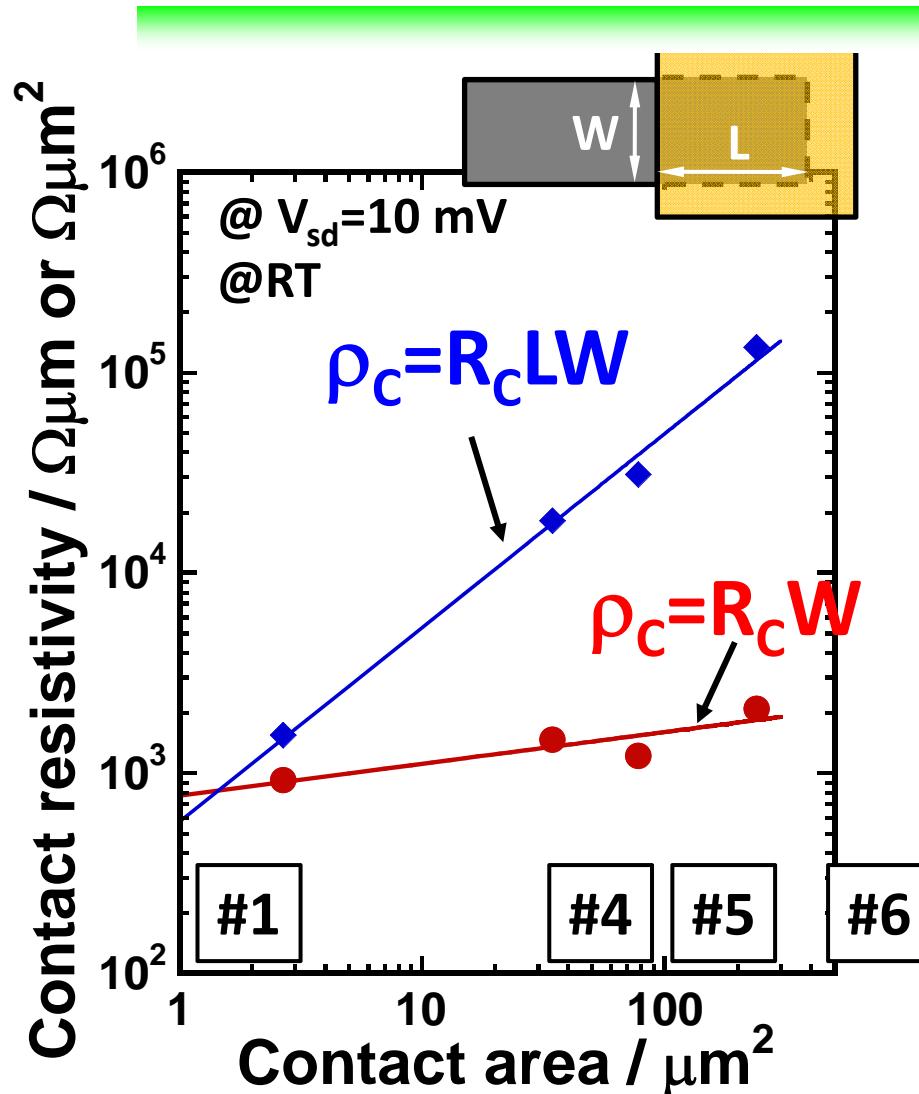
$$R_{total} = R_{ch} + 2R_{contact}$$

$$R_{contact} = \frac{1}{2} \left( R_{total} - \rho_{channel} \frac{L}{W} \right)$$

K. Nagashio et al., IEDM (2009).

*Contact area dependence of contact resistance.*

# *Current Crowding*



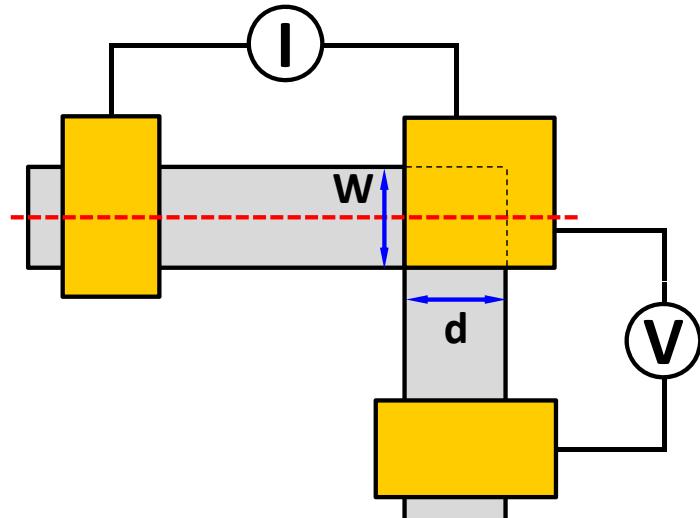
K. Nagashio et al., IEDM (2009).

*Current crowding should be considered in large contacts.*

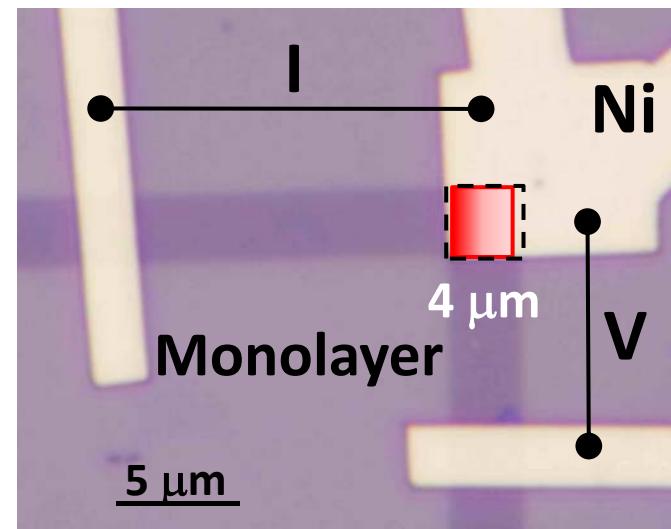
# *Specific Contact Resistance*

*Cross-bridge Kelvin*

$$R_c = \frac{V}{I} = \frac{\rho_{c\square}}{dW}$$



K. Nagashio et al., APL. 97(2010) 143514.



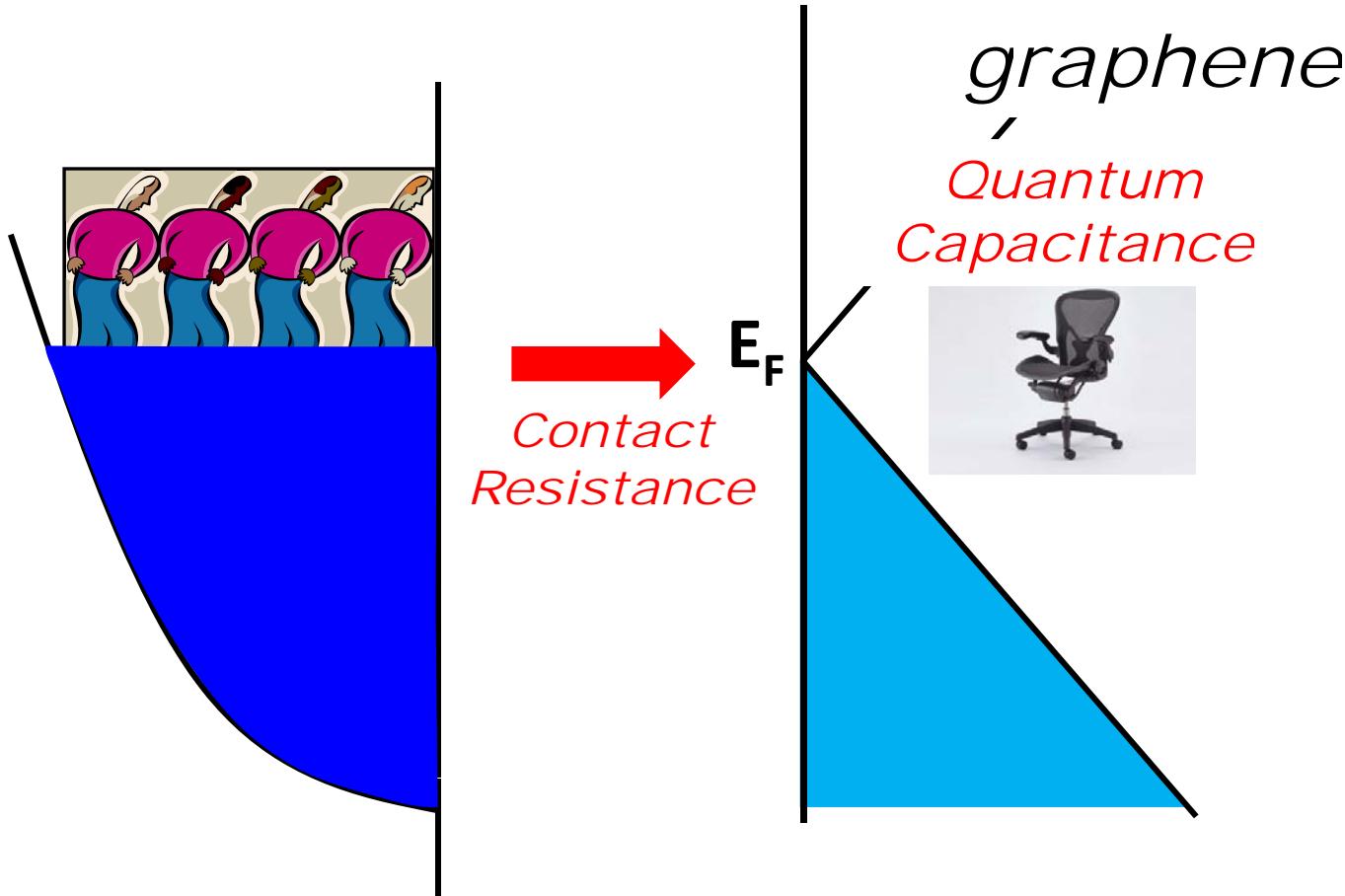
*Etched by  $O_2$  plasma*  
*contact resistivity*

$$\rho_{c\square} = \sim 5 \times 10^{-6} \Omega\text{cm}^2$$

*Transfer length*

$$d_T = \sqrt{\frac{\rho_{c\square}}{R_{sh}}} = \sim 1\mu\text{m}$$

# DOS Bottleneck

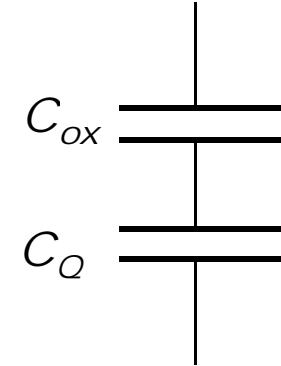
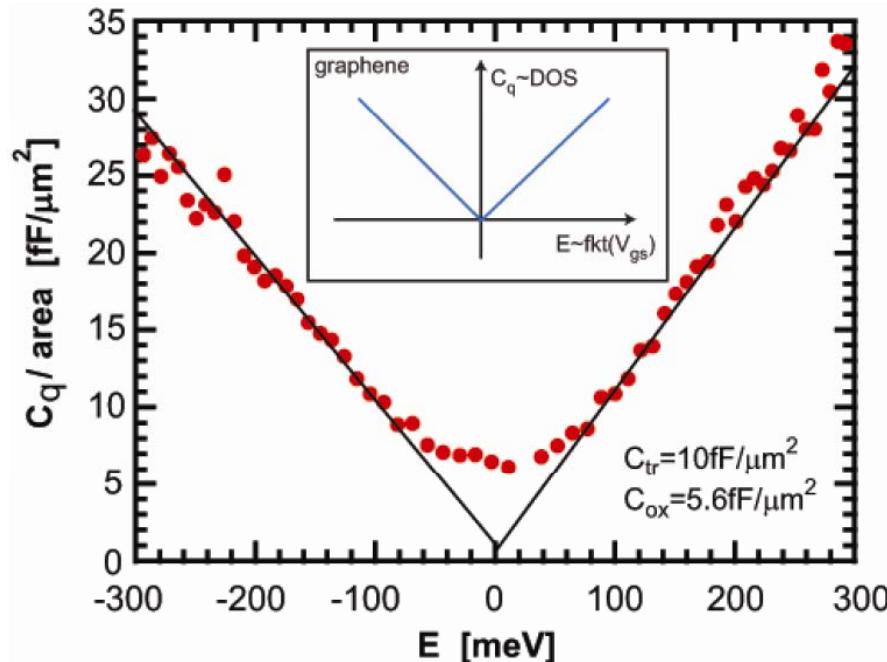


*A small number of seats available in the channel.*

## Intrinsic Challenges (3) - quantum capacitance -

$$C_q(V_g) = e^2 D(E) = e^2 \frac{2E_F}{\pi(v_F \hbar)^2}$$

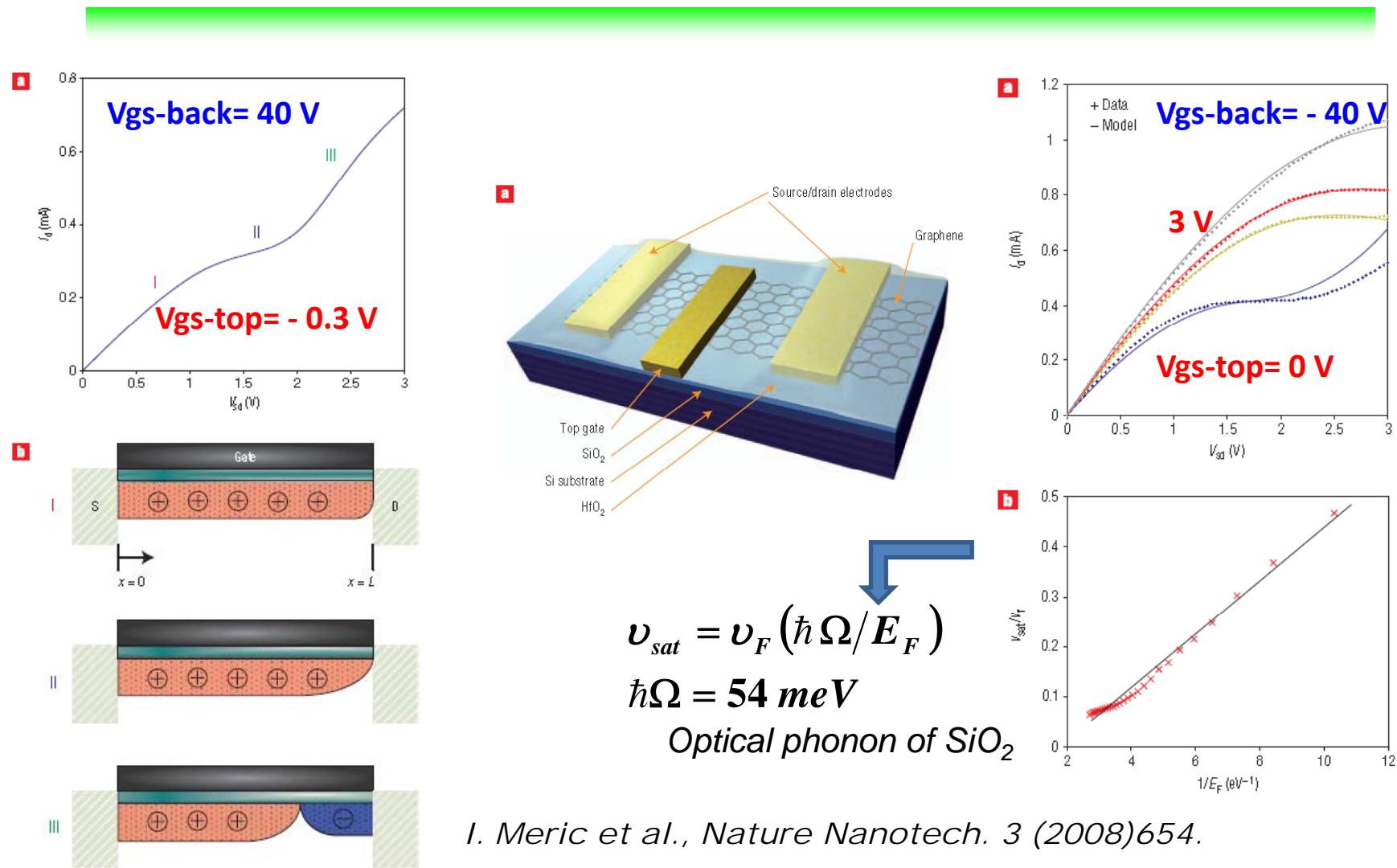
$$10 [fF/\mu m^2] \\ = 3.4 nm(EOT)$$



Z. Chen and J. Appenzeller, IEDM (2008)

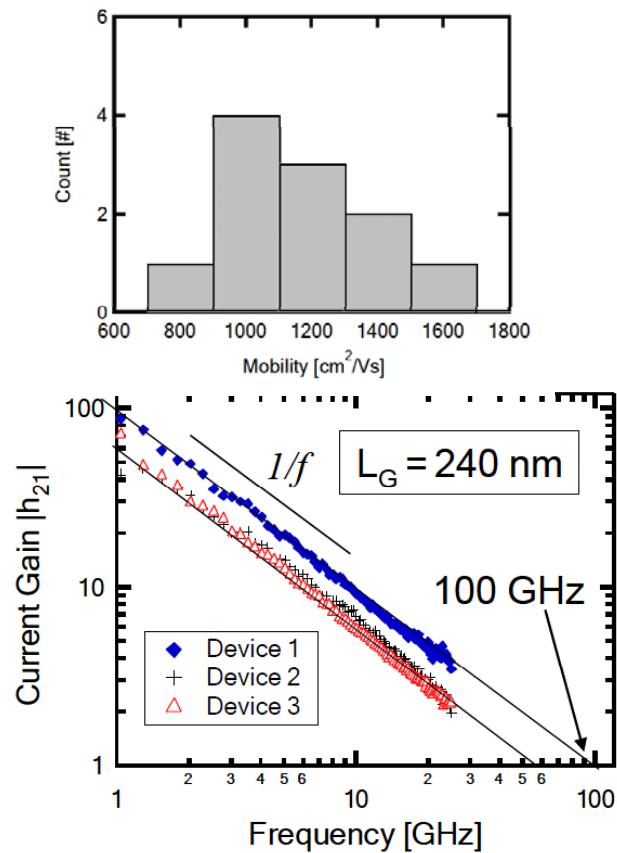
*Sub-nm CET is intrinsically difficult.*

# Output Characteristics



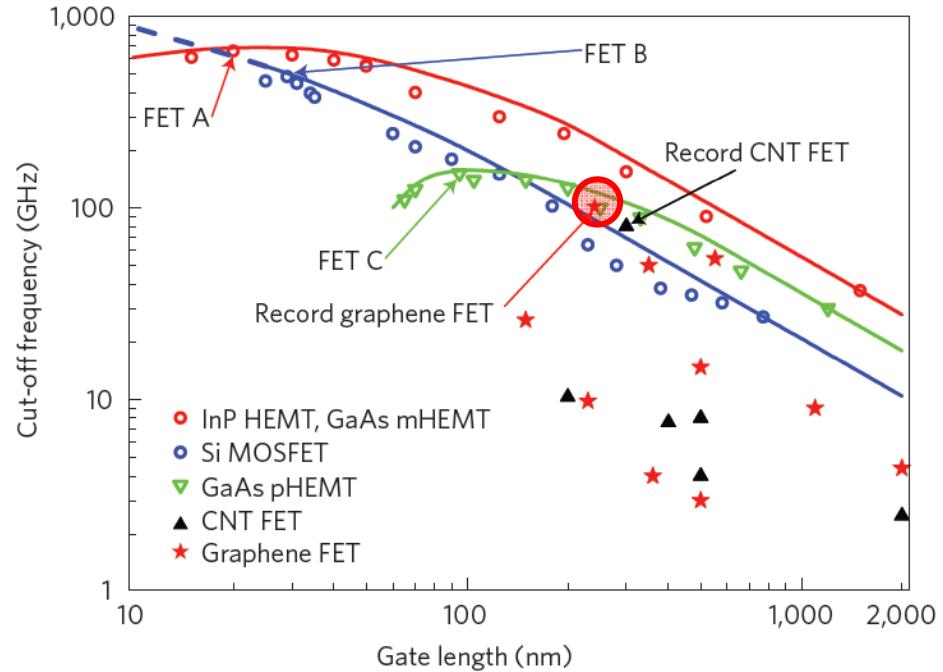
Intrinsically no pinch-off due to no band-gap.

# RF-Performance



*Y. M. Lin et al. Science 327(2010)662.*

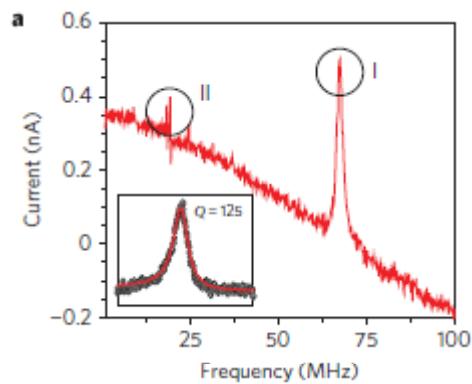
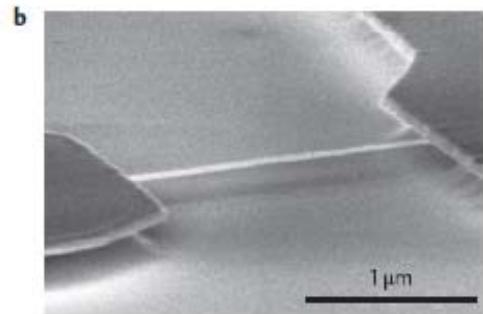
*F. Schwierz, Nature Nanotech. May 2010.*



*$f_T$  is comparable to existing RF devices.*

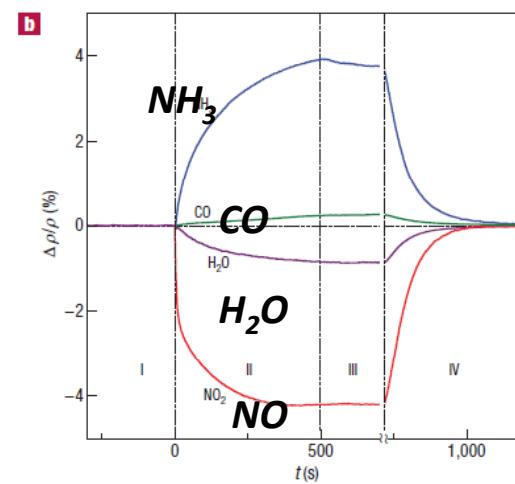
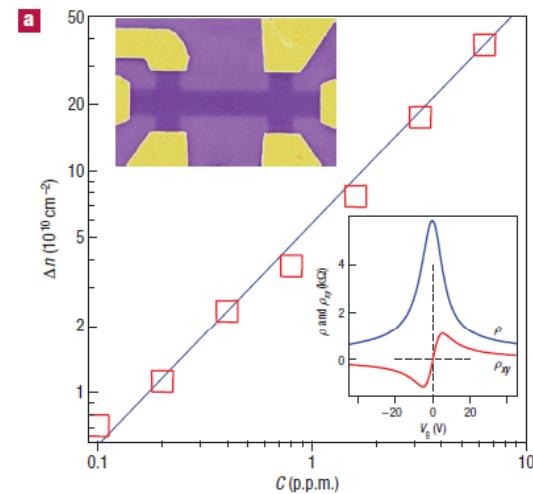
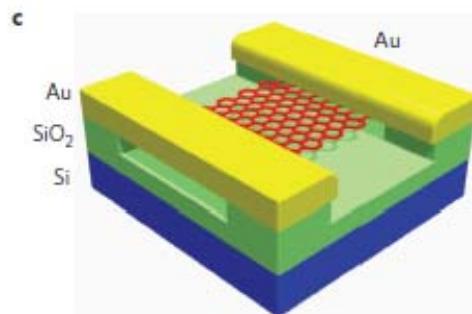
# Other Applications

## NEMS



C. Chen, et al., Nature Nanotech. 4 (2009)861.

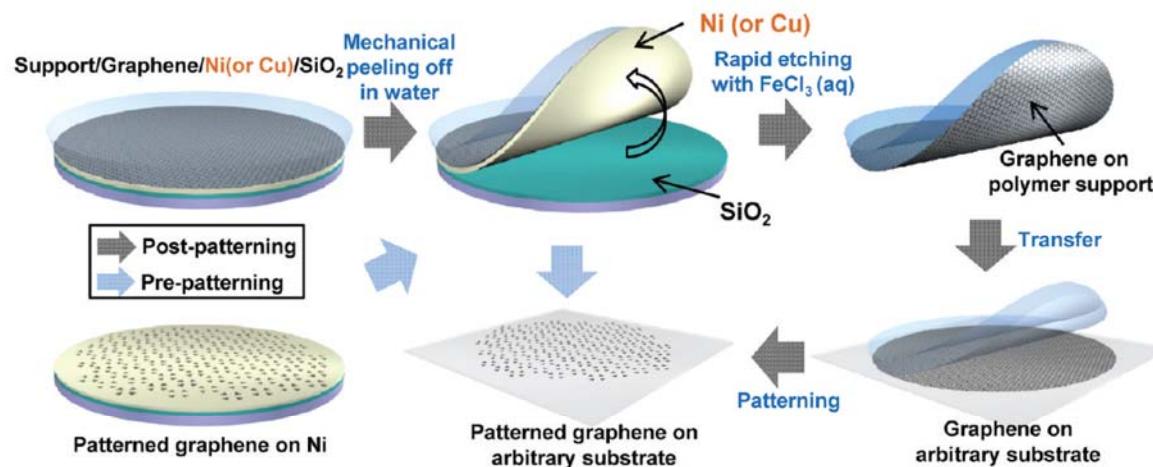
## Sensor



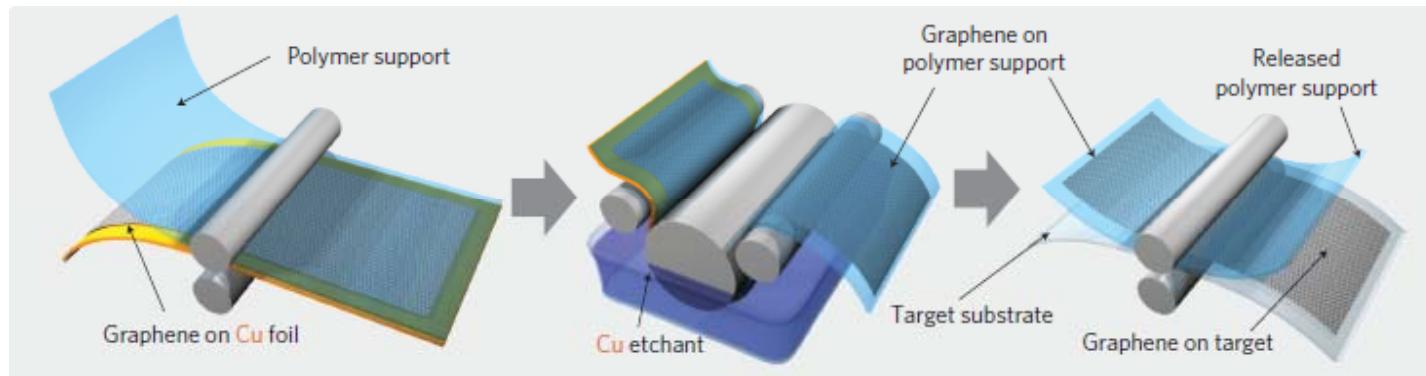
F. Schedin, et al., Nature Mater. 6 (2007)652.

# *Wafer Scale to Roll-to-Roll*

*SKKU + Samsung*



*Y. Lee et al., Nano Lett. 10 (2010) 490.*



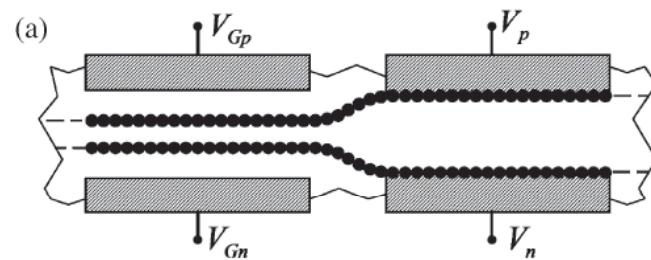
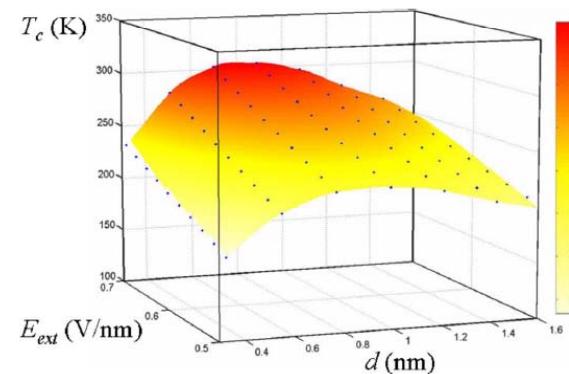
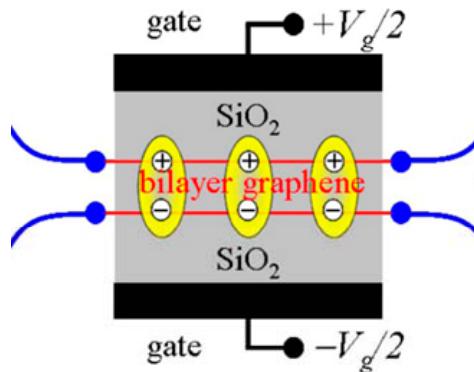
*S. Bae et al, Nature Nanotech. 5 (2010)574.*

# *Far Beyond Conventional FETs*

*BiSFET - Bilayer Pseudo Spin Field-Effect Transistor -*

*H. Min et al., Phys. Rev. B78 (2007)121401.*

*el-hole condensation through thin insulator.*



*S. K. Banerjee et al. IEEE EDL 30 (2009)158.*

*Bose condensation      contacts*

*Ultra-low Power Switching !*

# *Summary*



- ✓ Graphene is a really exciting material for both physicists and engineers.
- ✓ Monolayer graphene shows very high mobility for both electron and hole.
- ✓ High frequency application seems more promising than digital one.
- ✓ No band-gap and small DOS effects such as quantum capacitance and large contact resistance should be seriously concerned.
- ✓ *The graphene research is just booming up, and I believe it will shows different faces in a couple of years.*
- ✓ *Be optimistic about new materials for the present.*